Notice of Allowability	Application No.	Applicant(s)	
	10/625,610	KITAYAMA ET AL.	
	Examiner	Art Unit	
	Lynette T. Umez-Eronini	1765	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address--

All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. **THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS.** This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.

1. ☒ This communication is responsive to *8/11/2006*.

2. ☒ The allowed claim(s) is/are *16 and 18-21*.

3. ☒ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
   a) ☒ All b) ☐ Some* c) ☐ None of the:
      1. ☒ Certified copies of the priority documents have been received.
      2. ☐ Certified copies of the priority documents have been received in Application No. _____ .
      3. ☐ Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).

   * Certified copies not received: _____.

Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.
THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.

4. ☐ A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.

5. ☐ CORRECTED DRAWINGS (as "replacement sheets") must be submitted.
   (a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached
      1) ☐ hereto or 2) ☐ to Paper No./Mail Date _____.
   (b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date _____.

   Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).

6. ☐ DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.

Attachment(s)

1. ☐ Notice of References Cited (PTO-892)
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)
3. ☐ Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date _____
4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material
5. ☐ Notice of Informal Patent Application
6. ☐ Interview Summary (PTO-413), Paper No./Mail Date _____ .
7. ☒ Examiner's Amendment/Comment
8. ☒ Examiner's Statement of Reasons for Allowance
9. ☐ Other _____.

NADINE NORTON
SUPERVISORY PATENT EXAMINER
ART UNIT 1765

EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

Cancel non-elected claims 3-5 and 10-15.

2. The following is an examiner's statement of reasons for allowance:

As to claims 16 and 18-21, Applicants Remarks in Amendment filed 6/13/2006 was persuasive in showing the prior art of record fails to teach, suggest, or render obvious a polishing composition as defined by the claims as comprising a roll-off reducing agent comprising an inorganic compound as recited in the claims, in combination with the rest of the limitations of the claims.

Also, the prior art of record fail to teach, suggest, or render obvious a polishing composition, which comprises the specific combination of concentrations of inorganic compound, citric acid, water, and Al_2O_3 abrasive that is composed of an α-type corundum crystal, as defined by the claims.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably

accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Lynette T. Umez-Eronini whose telephone number is 571-272-1470. The examiner is normally unavailable on the First Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571-272-1465. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Art Unit 1765

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September 28, 2006

NADINE NORTON
SUPERVISORY PATENT EXAMINER
ART UNIT 1765

株式会社フジミインコーポレーテッド

FUJIMI

FUJIMI INCORPORATED

Polishing our technologies
and bringing people together.

Japanese ▸

Lapping & Grinding

Product information

A

Regular Fused Alumina

WA

White Fused Alumina

PWA

Platelet Calcined Alumina

A A is the most widely known abrasive powder, popularly called alundum. This product is made by melting bauxite in an electric furnace at a temperature of 2000℃ to obtain aluminumoxide (Al_2O_3) corundum crystal of at least 90% purity. One special feature of this product is that the toughness (tenacity) of the abrasive particles has been increased by fusing them with a small percentage of titanium. As a result, A has the highest degree of toughness among all Fujimi abrasive powders. This product, which is manufactured to sustain a consistent distribution of particle sizes, is a highly efficient abrasive and will not scratch the surface of the workpiece, and maintains great stability as it functions as an abrasive. A is well suited for use as a material in super-finishing precision grindstones and super-finishing lapping cloth or paper. It is the most suitable abrasive powder for use on cathode-ray tubes and related glassware, and soft metals, where precision lapping is required.

WA WA is a fused white alumina abrasive powder. It is a product with a wide variety of uses, and typical of the powders used in precision processing. It is produced by crushing fused alumina into a powder and then sorting the particles into a uniform size. WA has an α-type corundum crystal

configuration. It is a high-purity alumina, with at least a 96.0% pure Al_2O_3 • composition. It has a hardness next to that of silicon carbide (SiC), a closely controlled particle size distribution, a consistent particle shape, and has the potential to be used for high-level surface processing. WA has superior qualities for use as a material in super-finishing precision grindstones, super-finishing lapping cloth or paper, and lapping tape for super-precision surface finishing. It is also well suited for precision lapping of such materials as metals, quartz crystal and semiconductors with low tensile strength.

PWA PWA is a high-quality alumina-type abrasive powder, consisting of a plate-shaped crystal of $Al_2O_3$with a purity of over 99.0%. It has excellent heat-resistant properties as well as being chemically inert, and is not corroded by either acids or alkalis. As the particle size distribution of PWA is tightly controlled, it can produce a very fine lapped surface, giving it superlative effectiveness as an abrasive. With a tremendous range of utilizations, PWA is an abrasive powder capable of performing a myriad of functions. In addition to being suitable as a lapping agent for silicon, optical materials, liquid crystal, stainless steel and other metals, PWA is also ideal for use as a filler material for coatings, as a material for coating lapping cloth or paper, and as a compounding agent combined with a metal or synthetic resin.

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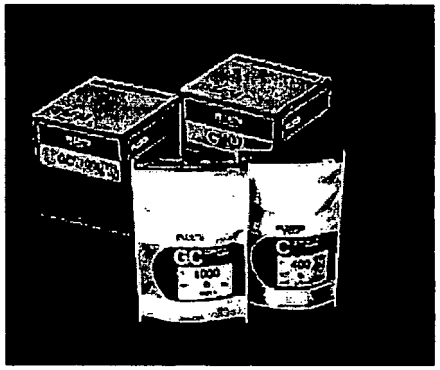
Product information

GC

Green Silicon Carbide

C

Black Silicon Cabide



GC GC, green silicon carbide, is a very high purity SiC lapping powder. The hexagonal α-type crystal is just below diamond in terms of hardness, and its chemical stability is excellent at room temperature. The result is a product with superior lapping and polishing capabilities, which is not

affected by chemicals, and can spontaneously generate sharp grinding edges through fragmentation. GC is well suited for use as a lapping powder in a wide range of functions, including the precision lapping and dicing of crystal and ferrite, the slicing of Si ingots, and the processing of materials ranging from ultra- hard metals and edged tools to soft metals such as brass and other copper alloys. Additionally, GC is used in the processing of various resins. GC is also ideal for use in super-finishing precision grindstones. As it possesses the electricalproperties of a semiconductor, GC has good heat conductivity and has the ability to withstand high temperatures, making it useful as a material in fine ceramics.

C C is a black silicon carbide lapping powder, commonly known as carborundum. Like GC, this product is obtained by fusing silica and coke in an electric furnace at a temperature of more than 2000°C, resulting in a product with an α-type silicon carbide crystal configuration. Although in comparison with GC, C is slightly lower in purity and hardness, it does have excellent toughness. C is manufactured using Fujimi's own unique production methods. Becauseof its stable cutting edges and its ideal particle size distribution, it is used for abrasive machining. The unique abrasive character of C makes it possible for superior lapping to be done on a work surface. C is ideal for use as a material for precision lapping polishing cloths and papers, and finishing precision grindstones. In addition, it can also be used for precision lapping of cast iron, brass, copper, aluminum, stone, and glass for photomasks. It is also well suited for the precision honing and dicing process necessary for such products as semiconductor crystals.

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